



LFW

Docket No.: SON-2769
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Hidetoshi OHNUMA, *et al*

Application No.: 10/603,689

Confirmation No.: 2872

Filed: June 26, 2003

Art Unit: 1756

For: EXPOSURE METHOD, MASK
FABRICATION METHOD, FABRICATION
METHOD OF SEMICONDUCTOR DEVICE
AND EXPOSURE APPARATUS

Examiner: D. D. Chacko

RESPONSE TO FINAL OFFICE ACTION

MS AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

This is in response to the Office Action dated July 25, 2006.

Remarks/Arguments begin on page 2 of this paper.